

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-13. (Canceled)

14. (Currently Amended) An exposure apparatus comprising:

a projection optical system from which an exposure light is radiated onto a substrate through a liquid to expose the substrate;

a liquid supply system which supplies the liquid;

a liquid recovery system which recovers the liquid; and

a substrate stage which holds the substrate, wherein:

a magnitude of a velocity of movement of the substrate stage ~~differs depending on a distance between a first position and a second position when the substrate stage is moved substantially linearly from the first position to the second position in a state in which a liquid immersion area is locally formed on the substrate stage by using the liquid supply system and the liquid recovery system, for moving the substrate stage substantially linearly from a first position to a second position in a state in which a liquid immersion area is locally formed on the substrate stage by using the liquid supply system and the liquid recovery system, is decreased when a distance between the first position and the second position is not less than a predetermined amount, as compared with when the distance between the first position and the second position is less than the predetermined amount.~~

15. (Canceled)

16. (Currently Amended) An exposure apparatus comprising:

a projection optical system from which an exposure light is radiated onto a substrate through a liquid to expose the substrate;

a liquid supply system which supplies the liquid;

a liquid recovery system which recovers the liquid; and  
a substrate stage which holds the substrate, wherein:  
~~a magnitude of a velocity of movement of the substrate stage differs depending on a direction of movement of the substrate stage from a first position to a second position when the substrate stage is moved substantially linearly from the first position to the second position in a state in which a liquid immersion area is locally formed on the substrate stage by using the liquid supply system and the liquid recovery system. for moving the substrate stage substantially linearly from a first position to a second position in a state in which a liquid immersion area is locally formed on the substrate stage by using the liquid supply system and the liquid recovery system, is decreased when the substrate stage is moved in a predetermined direction, as compared with when the substrate stage is moved in a direction different from the predetermined direction.~~

17. (Canceled)

18. (Currently Amended) The exposure apparatus according to claim 17,  
claim 16, wherein no liquid recovery port of the liquid recovery system is arranged at a side of a space under the projection system in the predetermined direction.

19-38. (Canceled)

39. (Currently Amended) An exposure method comprising:  
exposing a substrate by radiating an exposure light beam onto the substrate through a liquid; and

moving the substrate from a first position to a second position while retaining the liquid on the substrate; and substrate;  
~~adjusting a magnitude of a velocity of movement of the substrate from the first position to the second position depending on a positional relationship between the first position and the second position.~~

wherein a magnitude of a velocity of movement of the substrate from the first position to the second position is decreased when a distance between the first position and the second position is not less than a predetermined distance, as compared with when the distance between the first position and the second position is less than the predetermined distance.

40. (Canceled)

41. (Currently Amended) ~~The exposure method according to claim 39, An~~  
exposure method comprising:

exposing a substrate by radiating an exposure light beam onto the substrate through a liquid; and

moving the substrate from a first position to a second position while retaining the liquid on the substrate,

wherein the magnitude of the a magnitude of a velocity of movement of the substrate from the first position to the second position is decreased when the substrate is moved in a predetermined direction as compared with when the substrate is moved in a direction different from the predetermined direction.

42-48. (Canceled)

49. (Previously Presented) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 14; and  
processing the substrate to form the device.

50. (Previously Presented) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 16; and  
processing the substrate to form the device.

51-53. (Canceled)

54. (Previously Presented) A method for producing a device, comprising:  
exposing a substrate by the exposure method of claim 39; and

processing the substrate to form the device.

55. (Previously Presented) The exposure apparatus according to claim 14, wherein the liquid immersion area formed on the substrate stage includes a liquid immersion area on the substrate held on the substrate stage.

56. (Currently Amended) The exposure apparatus according to claim 14, wherein when the distance between the first position and the second position is not less than ~~a predetermined distance, the predetermined amount~~, the magnitude of the velocity of movement of the substrate stage is decreased such that the liquid is prevented from ~~leaking from the liquid immersion area~~ leaking.

57. (Currently Amended) The exposure apparatus according to claim 16, wherein when the substrate stage is moved in ~~a predetermined~~ the predetermined direction, the magnitude of the velocity of movement of the substrate stage is decreased such that the liquid is prevented from ~~leaking from the liquid immersion area~~ leaking.

58. (Currently Amended) The exposure method according to claim 39, wherein the magnitude of the velocity of movement of the substrate is decreased such that the liquid is prevented from ~~leaking from a liquid immersion area formed on the substrate~~ leaking.

59-60. (Canceled)

61. (Previously Presented) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 56; and  
processing the substrate to form the device.

62. (Previously Presented) A method for producing a device, comprising:  
exposing a substrate with the exposure apparatus of claim 57; and  
processing the substrate to form the device.

63. (Canceled)

64. (Previously Presented) A method for producing a device, comprising:

exposing a substrate by the exposure method of claim 41; and  
processing the substrate to form the device.

65. (Previously Presented) A method for producing a device, comprising:

exposing a substrate by the exposure method of claim 58; and  
processing the substrate to form the device.

66. (New) The exposure method according to claim 41, wherein the magnitude of the velocity of movement of the substrate is decreased such that the liquid is prevented from leaking.

67. (New) The exposure method according to claim 41, wherein the magnitude of the velocity of movement of the substrate is decreased such that a liquid immersion area locally formed on the substrate is maintained.

68. (New) The exposure method according to claim 41, wherein the magnitude of the velocity of movement of the substrate is decreased such that no gas portion is formed in a liquid immersion area locally formed on the substrate.

69. (New) The exposure method according to claim 41, wherein the substrate is linearly moved from the first position to the second position.

70. (New) The exposure method according to claim 39, wherein the magnitude of the velocity of movement of the substrate is decreased such that a liquid immersion area locally formed on the substrate is maintained.

71. (New) The exposure method according to claim 39, wherein the magnitude of the velocity of movement of the substrate is decreased such that no gas portion is formed in a liquid immersion area locally formed on the substrate.

72. (New) The exposure method according to claim 39, wherein the substrate is linearly moved from the first position to the second position.

73. (New) The exposure method according to claim 39, wherein the predetermined amount is determined based on affinity of the substrate for the liquid.

74. (New) The exposure apparatus according to claim 14, wherein the magnitude of the velocity of movement of the substrate is decreased such that a liquid immersion area locally formed on the substrate is maintained.

75. (New) The exposure apparatus according to claim 14, wherein the magnitude of the velocity of movement of the substrate is decreased such that no gas portion is formed in a liquid immersion area locally formed on the substrate.

76. (New) The exposure apparatus according to claim 16, wherein the magnitude of the velocity of movement of the substrate is decreased such that a liquid immersion area locally formed on the substrate is maintained.

77. (New) The exposure apparatus according to claim 16, wherein the magnitude of the velocity of movement of the substrate is decreased such that no gas portion is formed in a liquid immersion area locally formed on the substrate.